IN THE CLAIMS

This listing of claims replaces all prior listings:

 (Currently Amended) A method of manufacturing a diffusing reflector comprising the processes of:

preparing a substrate;

forming a first resin film having photosensitivity on said substrate;

providing a gathering of <u>adjacent</u> pillar-shaped bodies isolated from each other through patterning of said resin film with photolithography;

deforming gently said adjacent pillar-shaped bodies through a reflow;

forming an uneven surface layer having the maximum inclination angle of under 120 by coating with a thin layer of a second resin said gently deformed pillar-shaped bodies;

covering with the second resin open flat spaces located between said isolated <u>adjacent</u> pillar-shaped bodies to form one concave gap between <u>any</u> two adjacent isolated pillar-shaped bodies so that upper end portions of said <u>any</u> two adjacent isolated pillar-shaped bodies are higher than a lower end portion of said one concave gap in the thickness direction of the diffusing reflector, thereby minimizing an occurrence of a flat surface area on said substrate; and

forming a metal film on said uneven surface layer,

wherein.

said first resin film is patterned by straight connected lines that form a continuous polygonal pattern, said straight lines providing a <u>continuous and substantially uniform</u> gap between thereby formed <u>said</u> polygonal pillar-shaped bodies thereby forming a rectilinear honeycomb-like pattern, and

said gap having a size equal to about a minimum resolution of said photolithography, and

a thickness of the second resin is about 500nm.

2. (Previously Presented) The method of manufacturing a diffusing reflector as claimed in claim 1, wherein said maximum inclination angle is about 10° .

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- 3. (Cancelled)
- (Previously Presented) The method of manufacturing a diffusing reflector as claimed in claim 1, wherein said reflow process is a heat treatment under the temperature of about 220°C.
- 5. (Previously Presented) The method of manufacturing a diffusing reflector as claimed in claim 1, wherein gathering of polygonal pillar-shaped bodies isolated from each other by the divided patterning of said first resin film by said photolithography is provided.
 - 6. (Cancelled)